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AFM probe heated by absorbing laser radiation, What can we expect for the study of IR lasers?



Richard Arinero, Alexei Baranov and loffe Institute, St Petersbourg in the frame of LIA ILNACS

NAUOUIL



World leader in III-Sb technologies (GaSb, InAs, AlSb, InSb...)

effective band gaps particularly well suited to the mid-infrared (mid-IR~2 – 12 μ m)



- Gas analysis (pollution or process monitoring, physics of gases, of the atmosphere,...),
- Medical applications (surgery, diagnosis,..),
- Free-space communications
- Security- and defense-related applications (detection of toxic or explosive species,...)

An actual task is to investigate the <u>local complex spatial mode</u> <u>structure</u> and <u>the power of light</u> emerging from the <u>active zone</u>, which sometimes requires <u>high</u> <u>spatial resolution</u>.



Many applications

Actual Detectors

InSb: high sensitivity up to λ = 5 μ m

Possible coupling with optical fibered probes (as in "classical" scanning near-field optical microcopy (SNOM)) to collect the near-field light



Between 5 and 12 μm: MCT detectors



Beyond 12 μ m actual detectors performances become too poor to be used for SNOM of the lasers emitting in this range and suitable optical fibers are not available

AFM Probe: a thermal sensor?



t - thickness, w - width, I – length and the Young modulus (E) of the cantilever

Si or Si₃N₄

Possible coating on reflector and/or tip side (Al, Au, Ptlr, Cr, W₂C...)

When heated by ΔT , the <u>linear dimensions and</u> <u>Young modulus</u> of the cantilever change:

 $\Delta l/l = \Delta w/w = \Delta t/t = \alpha \Delta T$ α : Thermal expansion coefficient

 $\Delta E/E = \beta \Delta T$ β : Young modulus temperature coefficient

1. Bilayer or multilayer thermal effect

MFMR





Au (79 GPa, α=14.2×10⁻⁶ K⁻¹)

Stoney 1909 P. Roy Soc London Vol 82

Si <110> (169 GPa, α=2.59×10⁻⁶ K⁻¹)



Sensitivity ~ few pN/mK Low temperature variation difficult to detect with standard AFM in static mode

Each macropulse excites the resonance of the cantilever

$\boldsymbol{\lambda}$ in the far-IR to THz domain

Possible graphite layer on tip side to enhance Light absoption

pulses 5 ps long in macropulse trains of 8 μs at 25Hz and cover the range of 4–150 μm

Tunable free- electron laser (FEL)

Ortega et al APL 101 (2012)





Beam profile at λ = 37 µm using the cantilever. RMS size is approximately 2mm

2. Modification of dynamic response



Si: $\alpha \sim 10^{-6} \text{ K}^{-1} << \beta \sim 10^{-4} \text{ K}^{-1}$

Negative frequency or phase shift

$$\frac{\Delta\omega_0}{\omega_0} \approx -0.3 \times 10^{-4} \Delta T \qquad \Delta\phi \approx 2Q \frac{\Delta\omega_0}{\omega_0} \qquad \Delta\phi_{\min} \approx 0.1^{\circ}$$

Under vacuum (~ 10⁻⁶ mbar) : Q = 20000



 $\Delta T(\min) \approx 1.5 mK$

Temperature equalization time versus scan velocity



Thermal diffusivity of Si $\chi = 0.9 cm^2 / s$

 $\tau \approx 0.45 ms$

T(time between 2 pixels) = Time to scan one line/number of measurement points per line





Estimation of absorbed power and temperature increase

Maximum absorbed power (if the probe interacts with all the optical power)

$$P_{abs} = P(1 - e^{-\alpha h})$$

$$\approx 0.03 \, mW$$

 α = 100 cm⁻¹ absorption coefficient of IR-radiation by free electrons in silicon

h = 15 μ m tip height

Same WGM laser pumped at 45 mA



Spatial resolution ~0.3-0.4 µm !

Much lower than tip dimensions !

radial distribution of thelasing WG mode in theplane of cleavage

+

emission pattern modulated by a series of weak equidistant lines

 $\Delta = 0.7 \ \mu m$ = wavelength inside the waveguide (effective refractive Index ≈ 3.5)

Evanescent and propagating waves



Evanescent and propagating waves





« Ridge » GaSbbased diode lasers emitting at 2.1 μm
I = 16.5 mA
P = 1 mW

The <u>0.8 µm</u>-thick active region of the devices contained two GaInSbAs/GaAlSbAs quantum wells

Periodic lines $\Delta \sim 4.5 \ \mu m$



active zone



With an increase of $\Delta z = \lambda/2$ lines are shifted by one period

Analysis of LIFS intensity

Z =

2µm



16

Analysis of LIFS intensity



- 1. Au coating on tip side reduces the detected signal (reflection of radiation)
- 2. Signal is mainly due to absorption in the bulk and the top layer (the radiation absorption by silicon is weak at 2.1 μ m and Si₃N₄ is transparent)
- 3. Signal is stronger with Si₃N₄ than Si : Why ?

Sensitivity

Thermal conduction: Fourier's law in permanent regime



High sensitivity of Si₃N₄ probes is mainly due to the poor heat spreading because of the thermal conductivity and the small cross section of the cantilever.





μm

20



$$\frac{dF_{sc}}{dz} < 0$$

Positive Frequency shift !

Other techniques

March 1, 2014 / Vol. 39, No. 5 / OPTICS LETTERS, Klein et al, Abbe Center of Photonics, Jena, Germany



Highly sensitive mode mapping of whispering-gallery modes by <u>scanning</u> <u>thermocouple-probe</u> <u>microscopy</u>

OH



Fig. 3. (a) Thermovoltage map of a WGM with two radial maxima, overlaid on the topographic image. (b),(c) Synchronously measured (b) transmission and (c) reflection through the excitation taper.

Apertureless Scannning Near Field Microscopy (aSNOM)

P.-A. Lemoine et al. / Materials Science and Engineering B 149 (2008) 270–274

<u>Conventional SNOM</u>: based on the use of optical fiber coupled to a probe with sub-wavelength aperture

Fibers not adapted to wavelengths > 5 μ m

aSNOM (or sSNOM: scattering SNOM): scattering of the near-field by the AFM tip Apex HgCdTe cooled



QCL at 7.7 μm



Perspectives

InAs/AISb quantum cascade lasers operating in the far infrared (near 20 μ m)

Wavelengths within the 4th atmospheric transparency windows, which would allow, for example, extending the spectroscopy application domain.

Actual task: work at ambient temperature and continuous regime

Studies at both low temperature ~80-140 K (pulsed regime) and ambient temperature (continuous regime)

Characterization of other kind of IR lasers (Vecsels...)

Improvement of IR absoption: graphene?, InSb?, InGaAs? Grown by MBE on tip side...

Improvement of spatial resolution: metal or III-V layer deposition or growth on tip side excluding tip apex

Correction of tilt angle in order to control light interference with cantilever